## PATENT APPLICATION

Sheet 1 of 2

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ha	1A	5,894,189	4/13/1999	Og	asawara et al.							
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Aur Aur	1 F	Kusunoki et a Top Bectrode	Kusunoki et al., "Increasing Emission Current from MIM Cathodes by Using an Ir-Pt-Au Multilayer Top Electrode", IEEE Transactions on Electron Devices, Vol. 47, No. 8, Aug 2000, pp. 1667-1672.									
M	18	Negishi et al., Vol. 36 (1997	Negishi et al., "High Efficiency Electron-Emission in Pt/SiOx/Si/Al Structure", Jpn. J. Appl. Phys., Vol. 36 (1997), pp L939-L941.									
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## PATENT APPLICATION

Sheet 2 of 2

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hor	2Q	Miyamoto et al IVMC'97 Kyon	., "MIS Emitter witi gju, Korea, 1997, p	h Epita pp. 226	xial CaF2 Layer as In -230.	- nsulat	tor", Technical Digest of		
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